Form PTO-1449 U.S. DEPARTMENT OF COMMERCE ATTY, DOCKET NO. SERIAL NO. PATENT AND TRADEMARK OFFICE (MODIFIED) 032026-0754 10/772,573 **APPLICANT** INFORMATION DISCLOSURE CITATION Luke J. Mawst, et al. **FILING DATE GROUP ART UNIT** (Use several sheets if necessary) 02/05/2004 2811 **U.S. PATENT DOCUMENTS EXAMI** FILING DATE DOCUMENT NER SUB-**CLASS** REF DATE NAME IF INITIA **CLASS** NUMBER APPROPRIATE 8/11/98 5,793,787 Meyer, et al. 2004-0061102 4/1/04 Tansu 0 3 2004 5.383,211 1/95 Van de Walle, et al. 6,621,842 9/03 **Dapkus FOREIGN PATENT DOCUMENTS** TRANSLATION **DOCUMENT** SUB-DATE **CLASS** REF COUNTRY NUMBER **CLASS** YES NO WO 01/29943 4/26/01 **PCT** OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) H. C. Casey, Jr., "Temperature dependence of threshold current density on InP-Ga_{0.28}In_{0.72}As_{0.6}P_{0.4} (1.3 μm) double heterostructure lasers," J. Appl. Phys., Vol. 56 (7), 1984, pp. 1959-1964. J. R. Meyer, C. A. Hoffman, F. J. Bartoli, and L. R. Ram-Mohan, "Type II-quantum well lasers for the midwavelength infrared," Appl. Phys. Lett., 67 (6), 1995, pp. 757-759. M. Kondow, T. Kitatani, S. Nakatsuka, M. C. Larson, K. Nakahara, Y. Yazawa, M. Okai, and K. Uomi, "GalnNAs: A novel material for long wavelength semiconductor lasers," IEEE J. Select. Topic Quantum Electronic., Vol. 3, 1997, pp. 719-730. A. F. Phillips, A. F. Sweeney, A. R. Adams, and P. J. A. Thijs, "Temperature Dependence of 1.3- and 1.5-µm Compressively Strained InGaAs(P) MQW Semiconductor Lasers," IEEE. J. Select. Topics Quantum Electron., Vol. 5, No. 3, May/June 1999, pp. 401-412. S. Sato and S. Satoh, "1.21 μm Continuous-Wave Operation of Highly Strained GalnAs Quantum Well Lasers on GaAs Substrates," Jpn. J. Appl. Phys., Vol. 38, 1999, pp. L990-L992.

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